

Electronic Supplementary Information

Nanoscale LuFeO_3 : Shape dependent ortho/hexa phase constitution and nanogenerator application

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1. Sewing Machine set up

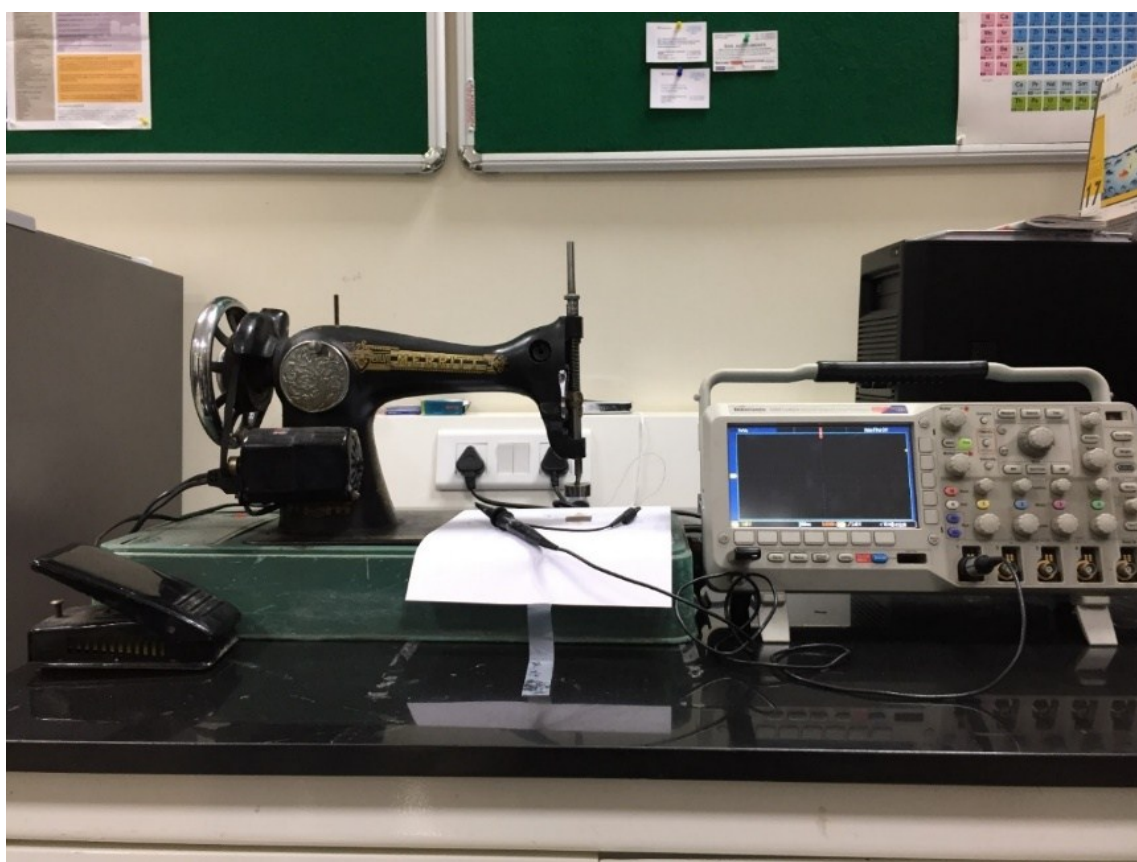


Figure S12. Sewing Machine set up for nanogenerator device measurement.

2. X ray diffraction and refinement

The diffraction patterns were collected in a 2θ angular range of $10-80^\circ$ with a step size of 0.009° . Total data acquisition time per scan was approx. 9 hours to ensure collection of diffraction patterns with good resolution and high signal-to-noise ratio. The lattice parameters and critical structural parameters were obtained by Rietveld refinement using the software FULLPROF SUITE. Instrumental broadening effects were determined by measurement of a NIST SRM 660c (LaB_6) sample under same conditions as all samples and compensated in all subsequent refinements.

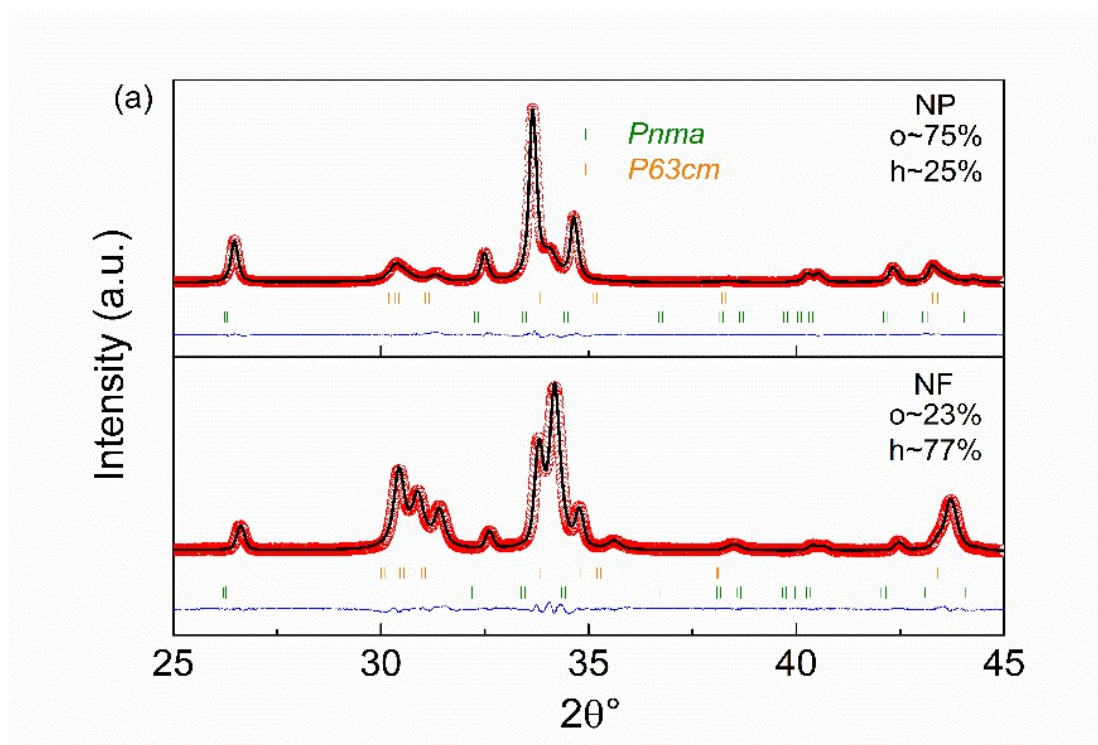


Figure S2 Showing refined XRD patterns for 2θ range 25 to 45.